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(54) PROMOTION OF EFFICIENCY IN PATCH CLAMP METHOD BY MICROPIPET POLISHING USING LOW TEMPERATURE IONIZATION PLASMA

(57) Abstract:

PURPOSE: To perform micropipet polishing in short time and also in large quantity by using a low temperature ionization plasma for the micropipet polishing in the patch clamp method.

CONSTITUTION: A micropipet is made from a thin tube, and a coating with a silicone resin is performed around the tip. The micropipet 2 thus obtained is put up in plural numbers in a glass laboratory dish 5 and placed in the chamber 6 of a plasma etching device for a semiconductor process for which a high frequency is used, and a hydrophilicity impartation by means of a oxygen plasma is performed. Then, the chamber 6 is filled with active species generated by the plasma. The micropipet thus obtained is provided with a giga-seal against living cells and artificial membranes and its probability is high.

